

Erratum

## Erratum: “Oxygen Enhanced Surface Roughening of Si(111) Induced by Low-Energy Xe<sup>+</sup> Ion Sputtering” [J. Surf. Anal. 15, 325 (2009)]

Takuya Miyagawa, Kousuke Inoue, and Masahiko Inoue\*  
Dept. Electric & Electronic Eng., Facult. Eng., Setsunan Univ.  
17-8 Ikedanakamachi, Neyagawa, Osaka 572-8508, Japan  
\*m-inoue@ele.setsunan.ac.jp

(Received: May 11, 2009; Accepted: May 13, 2009)

Figure 4 of the above paper should be replaced with the following figure.

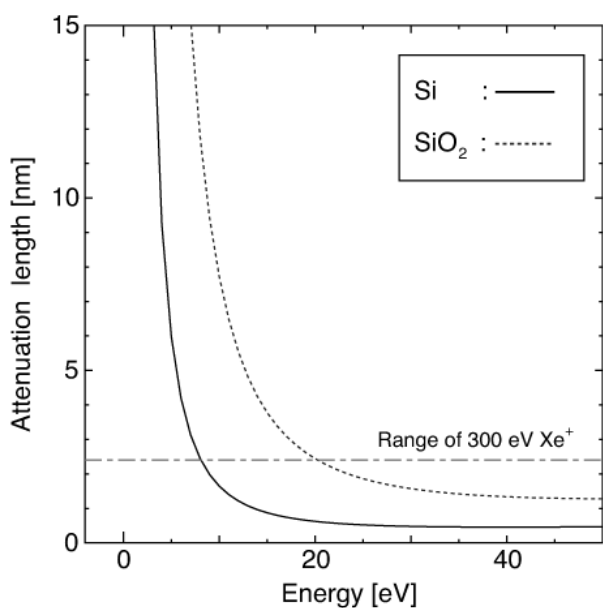


Fig.4 Attenuation lengths of secondary electrons evaluated by Seah & Dench’s equation [7] in Si and SiO<sub>2</sub> samples.